

Customer No.: 31561
Docket No.: 11439-US-PA
Application No.: 10/605,160

REMARKS

An editorial error of a reference number in the disclosure has been appropriately corrected.

Claim 7 has been amended, and the support of which can be found in originally filed claim 11. Since the amended limitation has been considered by the Examiner, such amendment does not necessitate new ground or new search. Accordingly, Applicant submits that if a next Office Action would be given based on new ground, such an Office Action should not be made final. Claim 9 has also been amended, in which only a grammatical informality is corrected.

As such, Applicant submits that the current application is now in a condition of allowance.

Claim Rejections 35 U.S.C. 102

Claims 11 and 12 are rejected under 35 U.S.C. 102(e) as being anticipated by Sandhu (US Pat. 6,752,912).

In response to the rejections thereto, Applicant hereby otherwise traverse this rejections. As such, Applicants submit that the color tunable panel, as set forth in claim 16 is novel and unobvious over Sandhu, or any of the other cited references, taken alone or in combination, and thus should be allowed.

With respect to claim 11, as originally filed, recites in parts:

An ionized physical vapor deposition (I-PVD) process, comprising the steps of:

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... the ionized metallic atoms are able to decelerate and form a metallic thin film on the wafer.

Applicant submits Sandhu failed to teach, suggest, or disclose, such process, comprising "the ionized metallic atoms are able to decelerate and form a metallic thin film on the wafer", as required by claim 11. Addressing the above limitation, the Examiner contended: "[T]he ionized metallic atoms pass through a conductive mesh before reaching a wafer such the ionized metallic atoms are able to decelerate due to the negative bias of the mesh 44 and 42" (Column 9, lines 5-62). However, on the contrary, in this part of cited reference, Sandhu teaches: "the grid 42 focuses the ions and the grid 44 accelerates the ions toward the substrate 12" (Column 9, lines 55-56). Therefore, one of ordinary skill in the art should understand that Sandhu teaches two grids 42, and 44, as a whole focuses and accelerates the ions, rather than decelerates the ions as required by claim 11. Since the each and every limitation of the invention, as set forth in claim 7 has not been taught, disclosed or suggested as is by Sandhu, or any of the other cited references, claim 11, and its dependent claim 12 are submitted to be novel and unobvious over Sandhu, or any of the cited references, taken alone or in combination, and thus should be allowed.

Claim Rejections 35 U.S.C. 103

Claims 7, 10, 13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sandhu in view of Katsuki et al. (US Pat. 5,728,276).

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In response to the rejections thereto, Applicant has amended claim 7 to include allowable subject matter presented in originally filed claim 11, which allowability has been discussed as aforementioned. As such, Applicant submits that claim 7 is also allowable.

With respect to claim 7, as currently amended, recites in part:

An ionized physical vapor deposition (I-PVD) process, comprising the steps of:

... the conductive mesh being applied with the smaller
negative bias voltage decelerates the ionized metallic atoms.

Similarly as discussed addressing to claim 11, Sandhu failed to teach, suggest, or disclose an process comprising: "the conductive mesh being applied with the smaller negative bias voltage decelerates the ionized metallic atoms". Therefore, claim 7 and its dependent claim 10 are submitted to be novel and unobvious over Sandhu, or any of the other cited references, taken alone or in combination, and thus should be allowed.

Claims 8 and 9 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sandhu, in view of Katsuki et al. as applied to claims 7, 10 and 13 above, and further in view of Givens et al. (US Pat. 5,807,467).

In response to the above rejections addressing claims 8, and 9, Applicants submit that claims 8 and 9 depend on allowable independent claim 7, and thus should also be allowable.

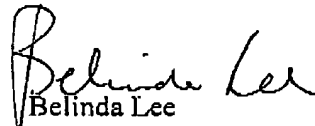
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CONCLUSION

For at least the foregoing reasons, it is believed that the pending claims 7-13 are in proper condition for allowance and an action to such effect is earnestly solicited. If the Examiner believes that a telephone conference would expedite the examination of the above-identified patent application, the Examiner is invited to call the undersigned.

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Respectfully submitted,


Belinda Lee

Registration No.: 46,863

Jianq Chyun Intellectual Property Office
7th Floor-1, No. 100
Roosevelt Road, Section 2
Taipei, 100
Taiwan
Tel: 011-886-2-2369-2800
Fax: 011-886-2-2369-7233
Email: belinda@jicpgroup.com.tw
Usa@jicpgroup.com.tw